

SHEET 1 of 3

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| INFORMATION DISCLOSURE CITATION PTO-1449 | Atty. Docket No. | Serial No. |
| | NTI-004 | 09/814,025 |
| | Applicant | |
| | KARKLIN, Linard | |
| | Filing Date | Group |
| | 3/20/2001 | 2623 |

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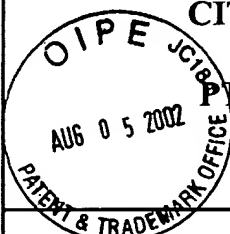
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| | | Applicant KARKLIN, Linard | | Group 2621 | | |
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| S.A ↓ | WO 97/13370 | 4/10/1997 | WO | | | <input type="checkbox"/> | <input type="checkbox"/> |
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| | WO 98/45685 | 10/15/1998 | WO | | | <input type="checkbox"/> | <input type="checkbox"/> |
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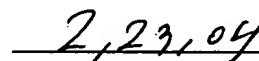
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CITATION**

PTO-1449

Atty. Docket No.

NTI-004

Applicant

KARKLIN, Linard

Filing Date

3/20/2001

Serial No.

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| | | | APPLICANT Karklin, et al. | | | |
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| | | | | | | YES | NO |
| S.A. | WO 00/36525 A3 | 6/22/00 | PCT | | | <input type="checkbox"/> | <input type="checkbox"/> |
| S.A. | WO 00/67074 A1 | 11/9/00 | PCT | | | <input type="checkbox"/> | <input type="checkbox"/> |
| S.A. | WO 00/67075 A1 | 11/9/00 | PCT | | | <input type="checkbox"/> | <input type="checkbox"/> |
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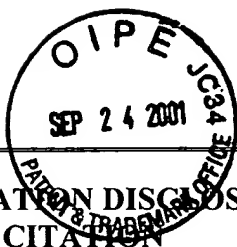
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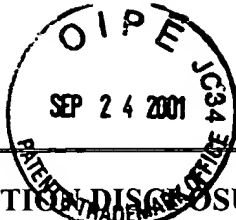
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